

2122



Docket No.: 5918/FPS/MMCS/APC/DV

PATENT/OFFICIAL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

SHANMUGASUNDRAM et al.

Serial No. 09/943,955

: Group Art Unit: 2122

RECEIVED

SEP 20 2002

Filed: August 31, 2001

: Examiner:

Technology Center 2100

For: FEEDBACK CONTROL OF A CHEMICAL MECHANICAL POLISHING DEVICE
PROVIDING MANIPULATION OF REMOVAL RATE PROFILES

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

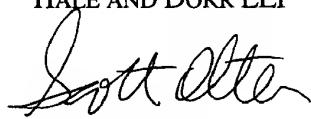
Serial No. 09/943,955

to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

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Date: 9/19/02

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 5918/FPS/MMCS/APC/DV	SERIAL NO. 09/942,955	RECEIVED SEP 20 2002 Technology Center 2100
				APPLICANT SHANMUGASUNDRAM et al.		
				FILING DATE August 31, 2001	GROUP 2122	
U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	4,698,766	10/06/87	Entwistle et al.			05/17/85
	4,967,381	10/30/90	Lane et al.			07/06/89
	5,208,765	05/04/93	Turnbull			07/20/90
	5,226,118	07/06/93	Baker et al.			01/29/91
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	5,812,407	09/22/98	Sato et al.			08/12/97
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	5,832,224	11/03/98	Fehskens et al.			06/14/96
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation
						Yes
	61-171147	08/01/86	Japan ↗			X
	6-184434	07/05/94	Japan ↘			X
	0 621 522 A2	10/26/94	Europe ↙			X
	8-50161	02/20/96	Japan ↘			X
	8-304023	11/22/96	Japan ↘			X
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	February 1984. "Method and Apparatus of in Situ Measurement and Overlay Error Analysis for Correcting Step and Repeat Lithographic Cameras." <i>IBM Technical Disclosure Bulletin</i> , pp. 4855-4859. ✓					
	October 1984. "Method to Characterize the Stability of a Step and Repeat Lithographic System." <i>IBM Technical Disclosure Bulletin</i> , pp. 2857-2860. ✓					
EXAMINER	DATE CONSIDERED					

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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	5,859,964	01/12/99	Wang et al.			10/25/96
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	6,148,246	11/14/00	Kawazome			06/10/98
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						Yes
	0 747 795 A2	12/11/96	Europe			X
	10-173029	06/26/98	Japan			X
	0 895 145 A1	02/03/99	Europe			X
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	Schmid, Hans Albrecht. 1995. "Creating the Architecture of a Manufacturing Framework by Design Patterns." Austin, Texas: OOPSLA.					
	Baliga, John. July 1999. "Advanced Process Control: Soon to be a Must." Cahners Semiconductor International. www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp					
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U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	6,175,777	01/16/01	Kim			01/16/98
	6,178,390	01/23/01	Jun			09/08/98
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	6,240,330	05/29/01	Kurtzberg et al.			05/28/97
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation
						Yes
	11-135601	05/21/99	Japan			X
	WO 00/05759	02/03/00	WO			X
	WO 00/35063	06/15/00	WO			X
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	July 5, 2001. "Motorola and Advanced Micro Devices Buy ObjectSpace Catalyst Advanced Process Control Product for Five Wafer fabs." Semiconductor FABTECH. www.semiconductorfabtech.com/industry.news/9907/20.07.shtml					
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APPLICANT
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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	6,240,331	05/29/01	Yun			08/18/98
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	6,345,315	02/05/02	Mishra			08/12/98
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	WO 00/79355 A1	12/28/00	WO			X	
	2001-76982	03/23/01	Japan				X
	WO 01/33501 A1	05/10/01	WO			X	

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